

Serial No. 10/044,358

In the claims:

1. (currently amended) An optoelectronic device, comprising:
an active region adjacent a first distributed bragg reflector (DBR) comprising a plurality of mirror periods wherein said mirror periods comprise a first layer formed from a first material having a first thermal conductivity and a second layer formed from a second material having a second thermal conductivity that is greater than said first thermal conductivity and, wherein the optical thickness of said first layer does not equal the optical thickness of said second layer for at least a portion of the plurality of mirror periods.
2. (currently amended) The optoelectronic device of claim 1 wherein the optical thickness of said first layers is one fourth of a wavelength of light emitted by said optoelectronic device and wherein the optical thickness of said second layers is an odd integer multiple of one fourth of the wavelength of the light emitted by said optoelectronic device, said odd integer multiple being greater than 1.
3. (currently amended) The optoelectronic device of claim 1 wherein the optical thickness of the second layer of at least said portion of mirror periods varies in a non-uniform fashion as a function of distance from said active region.
4. (original) The optoelectronic device of claim 3 wherein the mirror period in closest proximity to the active region comprises the thickest second layer.
5. (currently amended) The optoelectronic device of claim 4 wherein the optical thickness of the second layers decreases by an integer multiple of one half of a wavelength of light emitted by said optoelectronic device for mirror periods as a function of distance from said active region.
6. (original) The optoelectronic device of claim 1 wherein the optical thickness of said first layer is less than the optical thickness of said second layer and the sum of the optical

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thicknesses of said pair of layers is one half of a wavelength of light emitted by said optoelectronic device.

7. (original) The optoelectronic device of claim 1 further comprising a second DBR adjacent said active region.
8. (original) The optoelectronic device of claim 7 wherein said second DBR comprises a plurality of semiconductor mirror layers.
9. (original) The optoelectronic device of claim 7 wherein said second DBR comprises a plurality of dielectric mirror layers.
10. (original) The optoelectronic device of claim 7 wherein said second DBR comprises a hybrid mirror comprising a dielectric portion and a semiconductor portion.
11. (currently amended) The optoelectronic device of claim 1 wherein said active region comprises at least one quantum well ~~wells~~.
12. (currently amended) The optoelectronic device of claim 11 wherein said at least one quantum well comprises wells ~~comprise~~ GaAs.
13. (currently amended) The optoelectronic device of claim 11 wherein said at least one quantum well comprises wells ~~comprise~~ $\text{In}_{1-x}\text{Ga}_x\text{As}_{1-y}\text{N}_y$.
14. (original) The optoelectronic device of claim 1 wherein the first material comprises $\text{Al}_x\text{Ga}_{1-x}\text{As}$ and the second material comprises AlAs.
15. (original) The optoelectronic device of claim 14 wherein x equals zero.

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16-21. (canceled)

22. (currently amended) An optoelectronic device, comprising:
an active region formed adjacent a first distributed bragg reflector (DBR),
said DBR comprising a plurality of mirror periods wherein said mirror periods
comprise a first layer, formed from a first material GaAs having a first thermal conductivity
and a second layer, formed from a second material AlAs having a second thermal conductivity
that is greater than said first thermal conductivity,

wherein the optical thickness of at least a portion of said mirror periods is greater than
one-half wavelength of light emitted by said optoelectronic device, and further

~~The optoelectronic device of claim 21 wherein the optical~~ thickness of said first layers
is greater than the optical thickness of said second layers for at least said portion of said
mirror periods having a an optical thickness greater than one-half the wavelength of light
emitted by said optoelectronic device.

23-29. (canceled)

30. (previously added) An optoelectronic device comprising:
an active region; and
a distributed bragg reflector (DBR) adjacent said active region, said DBR comprising a
plurality of mirror periods wherein said mirror periods comprise a first layer formed from a
first material having a first thermal conductivity and a second layer formed from a second
material having a second thermal conductivity,

said second thermal conductivity being greater than said first thermal conductivity,
said plurality of mirror periods including a first mirror period adjacent said active
region,

said second layer of said first mirror period being adjacent said active region,

said second layer of said first mirror period having an optical thickness greater than an
optical thickness of said first layer of said first mirror period,

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each of said plurality of mirror periods having an optical thickness equal to a multiple of $\frac{1}{2}$ wavelength of light emitted by said optoelectronic device.

31. (previously added) The optoelectronic device of claim 30 wherein the thickness of said first layers is $\frac{1}{4}$ of a wavelength of light emitted by said optoelectronic device and wherein the optical thickness of said second layers is an odd integer multiple of $\frac{1}{4}$ of a wavelength of light emitted by said optoelectronic device.
32. (previously added) The optoelectronic device of claim 30 wherein the thickness of the second layer of at least a portion of said plurality of mirror periods varies in a non-uniform fashion as a function of distance from said active region.
33. (previously added) The optoelectronic device of claim 30 further comprising a second DBR adjacent an opposite side of said active region.
34. (previously added) The optoelectronic device of claim 33 wherein said second DBR comprises a plurality of semiconductor mirror layers.
35. (previously added) The optoelectronic device of claim 33 wherein said second DBR comprises a plurality of dielectric mirror layers.
36. (previously added) The optoelectronic device of claim 33 wherein said second DBR comprises a hybrid mirror comprising a dielectric portion and a semiconductor portion.
37. (previously added) The optoelectronic device of claim 30 wherein said active region comprises at least one quantum well.
38. (previously added) The optoelectronic device of claim 37 wherein at least one quantum well comprises GaAs.

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39. (previously added) The optoelectronic device of claim 37 wherein at least one quantum well comprises $\text{In}_{1-x}\text{Ga}_x\text{As}_{1-y}\text{N}_y$.
40. (previously added) The optoelectronic device of claim 30 wherein said first material comprises $\text{Al}_x\text{Ga}_{1-x}\text{As}$ and said second material comprises AlAs .
41. (previously added) The optoelectronic device of claim 40 wherein x equals zero.

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